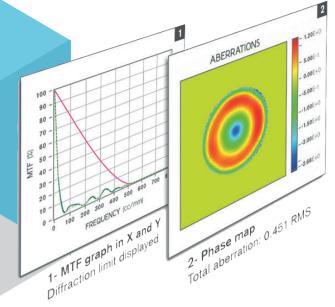


电话: 0755-84870203 邮箱: sales@highlightoptics.com



Simple measurement, advanced results

PHASICS offers the most innovative solutions for **quality control of lenses and complex optical systems in R&D and production**. Relying on a unique wavefront technology called quadriwave lateral shearing interferometry, PHASICS solutions provide **fast and complete characterization** of your optics.

IN A SINGLE ACQUISITION...

- ... GET THE MTF
- Along any direction
- For any pupil size
- On and off-axis
- Up to cut-off frequency
- With various focusing methods

... AND WAVEFRONT QUALITY

- EFL, F#, NA
- Aberrations: Zernike, Seidel
- Real-time filtering of phase map

(Zernike, Kernel...)

- Through focus MTF
- Comparison to design
- Chromatic aberrations

Kaleo products metrology of lenses and complex optical systems

35155



→ DIRECT MEASUREMENT

Measuring diverging and converging beams with no relay lens, PHASICS sensors enable a compact and direct set-up:

• Simple alignment

Same set-up to cover your

full optics range

 Characterization in working conditions

Easy measurement

interpretation

→ HIGH RESOLUTION

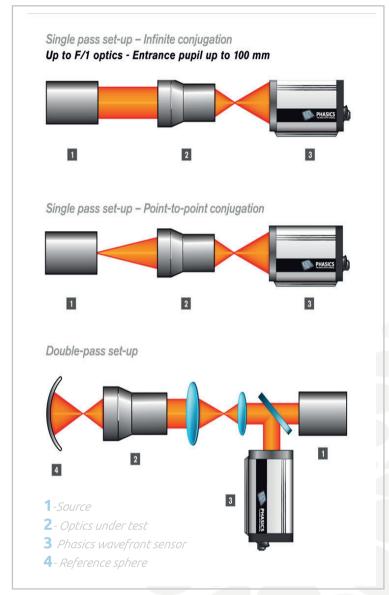
The unrivalled high resolution of PHASICS sensors ensure **reliability**, by enabling robust calculations and small defects detection. • Up to 300 x 400 measurement points • Nanometer-level axial resolution

→ HIGH DYNAMIC RANGE

PHASICS sensors measure **strongly aberrated optics** to detect non-compliant **sub-assemblies** before assembly. They also measure **aspheric lenses** in transmission.

→ STABILITY

PHASICS technology does not use any reference beam, making it **unsensitive to vibrations.**



Powerful technology

→ ACHROMATICITY

Inherently achromatic, PHASICS technology enables measurement **at any wavelength** without calibration:

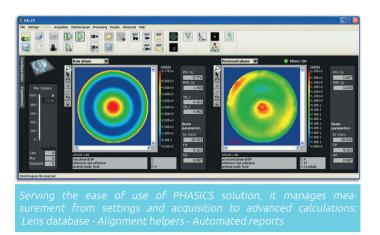
- Focus shift with wavelength
- MTF comparison at various wavelengths

\rightarrow EASY AND RIGOROUS ANALYSIS

The software solution ensures **reliable** calculation and offers **flexibility**:

 Focusing methods (best or paraxial focus, MTF autofocus)

- Pupil size
- Advanced filtering options

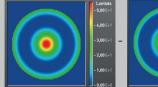


Direct phase measurement allows advanced analysis while **simplifying the result interpretation**.

Expert analysis software

DESIGNPRO MODULE

From the optical design file, this module simulates the nominal phase in the measurement plane and delivers the **residual wavefront error** (WFE)



Measured Phase PV=57.4λ -3,00E+1 -2,00E+1 -1,00E+1 -1,00E+1

Simulated wavefront

from Zemax design

Residual wavefront

MEASURED ELEMENTS

• Single lens, component

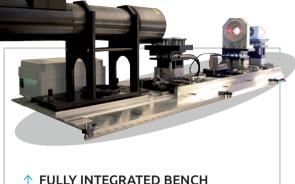
- Complex assembly, zoom lens
- Strongly aberrated sub-assembly

APPLICATIONS

- New product development
- Process optimization
- Cost-effective lens alignment

A full range of solutions for R&D and production





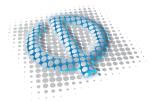
PHASICS provides OEM solutions combining wavefront sensor and software. PHASICS also designs benches fully dedicated to your needs. With a strong expertise in metrology, PHASICS works closely with your teams to analyze all your requirements (specification, throughput, budget...) and builds custom solutions mixing the right elements from

its large collection of solutions (alignment tools, choice of configuration and measurement conditions, analysis tools...) Dedicated software packages are developed on demand for easy insertion in your working environment, with special attention to safety standard compliance and ease of use for production.

	Spectral range	Aperture dimension (mm²)	Spatial resolution	Phase sampling (pixels)	Phase accuracy (Absolute)	Phase resolution	Vacuum compatibility
UV	250-400 nm	7.4 x 7.4	29.6 µm	250 x 250	10 nm RMS	2 nm RMS	-
SID4 V	400-1100 nm	4.73 x 3.55	29.6 µm	160 x 120	15 nm RMS	2 nm RMS	> 10 ⁻⁶ mbar
SID4	400-1100 nm	4.73 x 3.55	29.6 µm	160 x 120	10 nm RMS	2 nm RMS	-
SID4-HR	400-1100 nm	11.84 x 8.88	29.6 µm	400 x 300	15 nm RMS	2 nm RMS	-
NIR	1.5-1.6 µm	4.73 x 3.55	29.6 µm	160 x 120	15 nm RMS	11 nm RMS	-
SWIR	0.9-1.7 µm	9.6 x 7.68	120 µm	80 x 64	15 nm RMS	2 nm RMS	-
SWIR-HR	0.9-1.7 µm	9.6 x 7.68	60 µm	160 x 128	15 nm RMS	2 nm RMS	-
eSWIR	1.0-2.35 µm	9.6 x 7.68	120 µm	80 x 64	<40 nm RMS*	<6 nm RMS*	-
DWIR	3-5 μm & 8-14 μm	10.08 x 8.16	68 µm	160 x 120	75 nm RMS	25 nm RMS	-
LWIR	8-14 µm	16 x 12	100 µm	160 x 120	75 nm RMS	25 nm RMS	-

SID4 RANGE FROM UV TO IR

* For coherent sources





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